Electronic Supplementary Information (ESI)

Liquid-Phase Epitaxial Growth of Multiple MOF Thin Films with Highly

Lattice Mismatch

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Table of Contents

Materials and instrumentations

Preparation of MUD SAMs based substrates

Fabrication of SURMOFs on substrate surfaces

Scheme S1. The preparation setups for mono- varietal (a), bi-varietal (b) and tri-varietal) SURMOFs prepared by LEP layer by layer pump methods.

Figure S1. The preparation process of MUD SAMs.

Figure S2. IR spectra of SURMOF-a.

Figure S3. IR spectra of SURMOF-b.

Figure S4. IR spectra of SURMOF-c.

Figure S5. SEM images of SURMOF-a (a), SURMOF-b (b), SURMOF-c (c).

Figure S6. (a) Preparation process of **SURMOF-a on b**; out-of-plane (b) and in-plane XRD patterns (c) and as well as SEM image (d) of **SURMOF-a on b**.

Figure S7. (a) Preparation process of **SURMOF-b on a**; out-of-plane (b) and in-plane XRD patterns (c) and as well as SEM image (d) of **SURMOF-b on a**.

Figure S8. (a) Preparation process of **SURMOF-a on c**; out-of-plane (b) and in-plane XRD patterns (c) and as well as SEM image (d) of **SURMOF-a on c**.

Figure S9. (a) Preparation process of **SURMOF-b on c**; out-of-plane (b) and in-plane XRD patterns (c) and as well as SEM image (d) of **SURMOF-b on c**.

Figure S10. (a) Preparation process of **SURMOF-c on b**; out-of-plane (b) and in-plane XRD patterns (c) and as well as SEM image (d) of **SURMOF-c on b**.

Figure S11. IR spectra of SURMOF-a on b, SURMOF-a on b, SURMOF-c on a, SURMOF-a on c, SURMOF-b on c, respectively.

Figure S12. (a) Preparation process of **SURMOF-a on b on c**; out-of-plane (b) and in-plane XRD patterns (c) of **SURMOF-a on b on c**.

Figure S13. SEM images of SURMOF-c on b on a (a) and SURMOF-a on b on c (b).

Figure S14. IR spectra of SURMOF-c on b on a (a) and SURMOF-a on b on c (b).

Figure S15. The lattice constant mismatch analysis between **SURMOF-a** and **SURMOF-b** [(a2-a1)/a1] and between **SURMOF-a** and **SURMOF-c** [(a3-a1)/a1].

Materials and instrumentations

All of the chemicals were used after purchasing without further purification. Out-of-plane XRD measurements was carried out on Bruker D8 advance equipped with a Si-strip detector (PSD Lynxeye (C)) using Cu K_{α 1} radiation. In-plane XRD measurements were carried out using Bruker D8 Discover. IR spectra were recorded by using a using a FTIR spectrometer (Bruker VERTEX 80v). Scanning electron microscope (SEM) images for the morphology of thin films were recorded using a Philips XL30 (FEI Co., Eindhoven, NL) field emission gun environmental scanning electron microscope (FEG-ESEM). A Q-Sense E4 QCM was used to study the vapor adsorption of SURMOFs.

Preparation of MUD SAMs based substrates

Self-assembled monolayers (SAMs) were fabricated by immersing 150 nm Au/2 nm Ti/evaporated on Si wafers or commercially available Au substrates in ethanolic solutions of MUD (1mmol/L) (MUD=11-mercapto-1-undecanol). 1mM/L ethanolic solutions of MUD ethanolic solutions was used for SAMs preparation by 72 h immersion and then rinsed with ethanol and dried under nitrogen flux to obtain -OH group functionalized Au substrate.

Fabrication of SURMOFs on substrate surfaces

The SURMOFs used in the present work were grown using the layer by layer autoarm pump method. The -OH group functionalized Au substrates was put in the sample cell, and then subsequently filled with $Cu(OAc)_2$ and $H_2L/dabco$ (L = bdc, bpc and tpdc) ethanolic solutions in the sample cell for 30 min at 50 °C. There was 2 min ethanol washing in each step. Then 30 repeated cycles of preparation process resulted in the formation of homogeneous SURMOFs SURMOF-a, -b, -c.

For further prepare bi-varietal SURMOFs, the pre-prepared mono-varietal SURMOF was used for growth substrate, then this layer by layer pump process allows us to separately control the $Cu(OAc)_2$ and organic linker L2 deposition on the mono-varietal SURMOF to form bi-varietal SURMOF.

To prepare tri-varietal SURMOFs, the pre-prepared bi-varietal SURMOF was used for growth substrate, then this layer by layer pump process allows us to separately control the $Cu(OAc)_2$ and organic linker L3 deposition on the bi-varietal SURMOF to form tri-varietal SURMOF.



Scheme S1. The preparation setups for mono- varietal (a), bi-varietal (b) and tri-varietal) SURMOFs prepared by LEP layer by layer pump methods.



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Figure S4. IR spectra of SURMOF-c.



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